

a movable clamp for clamping an edge portion of the target object and holding the target object on the mounting table;

a second heating apparatus formed separately from the mounting table to surround the mounting table and arranged below the clamp to be opposite the clamp;

a first gas flow path formed between the mounting table and the second heating apparatus;

C1
a second gas flow path formed between the clamp and the second heating apparatus when the clamp is moved to a position where the clamp clamps the target object; and

C2
a second gas supply section for causing backside gas to flow into the first and second gas flow paths.

2. (Once Amended) The film deposition apparatus according to claim 1, wherein the first and second gas flow paths extend so as to pass the edge portion of the target object clamped by the clamp.

Please add new Claim 16 as follows:

16. (New) A film deposition apparatus comprising:

a container forming a processing chamber for processing a target object;

C2
a mounting table which is provided in the processing chamber and on which the target object is mounted,

a first heating apparatus provided in the mounting table,

g2
a first gas supply section provided in the container, for supplying processing gas into the processing chamber, the processing gas forming a thin film on the target object mounted on the mounting table;

a movable clamp for clamping an edge portion of the target object by an inner periphery of the clamp and holding the target object on the mounting table;

a second heating apparatus arranged below the clamp to be opposite to the clamp;

a gas flow path formed between the clamp and the second heating apparatus when the clamp is moved to a position where the clamp clamps the target object; and

C2
at a second gas supply section for causing backside gas to flow into the gas flow path to direct the gas to an outer periphery of the clamp.
